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[\[Image PDF \(6100K\)\]](#) [\[References\]](#)**Nanoimprint Technology**Yoshihiko HIRAI<sup>1)</sup>

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**Abstract**

Nanoimprint lithography is one of the promising technologies for ultra integration systems. This paper introduces some basic issues of this technology such as polymer deformation mechanisms, mold fabrication and its surface treatment. Also, fabrication of high aspect ratio nano structure, curved structures, bio-devices and 3-dimensional multilayered structure are demonstrated.

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